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Contents

NOVEL LITHOGRAPHY AND ALTERNATIVE PATTERNING III

POSTER SESSION

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

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Marco J. Wieland, MAPPER Lithography (Netherlands)
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Session Chairs

1 Keynote Session
Eric M. Panning, Intel Corporation (United States)
Martha I. Sanchez, IBM Research - Almaden (United States)

2 Invited Session: Scanning Probe Patterning
Chandrasekhar Sarma, Intel Corporation (United States)
Richard A. Farrell, TEL Technology Ctr., America, LLC (United States)

3 Novel Lithography and Alternative Patterning I
Ivo W. Rangelow, Technische University Ilmenau (Germany)
Marco Wieland, MAPPER Lithography (Netherlands)

4 Self-Assembly
Ricardo Ruiz, Western Digital (United States)
Laurent Pain, CEA-LETI (France)

5 E-beam Lithography
Ines A. Stolberg, Vistec Electron Beam GmbH (Germany)
Hans Loeschner, IMS Nanofabrication GmbH (Austria)

6 DSA Materials and Characterization: Joint Session with Conferences 10586 and 10584
Ralph R. Dammel, EMD Performance Materials Corporation (United States)
Chi-Chun Liu, IBM Corporation (United States)

7 DSA Materials and Integration: Joint Session with Conferences 10586 and 10584
Daniel Sanders, IBM Research - Almaden (United States)
J. Alexander Liddle, National Institute of Standards and Technology (United States)

8 Nanoimprint Lithography Masks and Systems
Tatsuhiko Higashiki, Toshiba Memory Corporation (Japan)
John G. Maltabes, Applied Materials GmbH & Company KG (United States)